



NOTES:

1. MATERIAL: UVFS
2. COATING (S1) : HIGH ENERGY LASER LINE COATING  
 $R_s, R_p > 99\% @ 532 \text{ nm}, 0^\circ - 45^\circ \text{ AOI}$
3. CLEAR APERTURE (S1) :  $> 90\%$  (CA)
4. SURFACE QUALITY (S1) : 20/10 (S/D)
5. SURFACE FLATNESS (S1) :  $\lambda / 10 @ 633 \text{ nm}$
6. PARALLELISM (S1, S2) :  $< 3 \text{ arcmin}$
7. CHAMFER:  $< 0.2 \text{ mm}, 45^\circ$
8. BACK SURFACE (S2) : POLISH

DRAWING PROJECTION			<b>LBTEK</b>			
	NAME	DATE	LPM20-532P-HP			
DRAWN	Lynne	JAN./12th/24	HIGH ENERGY LASER LINE MIRROR Ø 50.8 mm x 12 mm, 532 nm			
APPROVAL	CWZ	JAN./12th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	53.57g	3:2	A